

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant : Paul B. Mirkarimi et al. Docket No. : CIL-10972
Serial No. : 10/086,614 Art Unit : 1762
Filed : March 1, 2002 Examiner : A. Bashore
For : Ion-Assisted Deposition Techniques for
the Planarization of Topological Defects

RESPONSE

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Dear Sir:

Please consider the following remarks in response to the Office Action mailed
September 25, 2007: